

[Document Name] Abstract

[Abstract]

[Task] To provide a monomer that can become a raw material of a base polymer for resist materials and optical materials that are required to be low in light scattering and absorption and to be high in transparency.

[Solving Means] A fluorine-containing allyl ether compound represented by the following general formula 1.

[Chem. 1]



(In the formula, R represents an organic group containing at least one fluorine atom and having an alicyclic structure.)

A fluorine-containing allyl ether of the present invention can be copolymerized with monomers, such as α -trifluoromethyl acrylic esters and acrylic esters, that are useful for resist resins.

[Selected Drawing] None